

International Symposium on Extreme Ultraviolet Lithography 2008

(2008 EUVL Symposium)

**Lake Tahoe, California, USA
28 September – 1 October 2008**

Volume 1 of 3

ISBN: 978-1-61567-661-3

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TABLE OF CONTENTS

Volume 1

OPENING PRESENTATIONS

Welcome to the 2008 EUVL Symposium!	1
<i>Stefan Wurm, Ichiro Mori, Rob Hartman</i>	
Program Logistics & Overview	10
<i>Obert Wood, Patrick Naulleau</i>	
EUV Lithography's Future	21
<i>Harry J. Levinson</i>	
Samsung Lithography Strategy	71
<i>Woosung Han</i>	
EUV Activities the EUVL Shop Future Plans	97
<i>Rob Hartman</i>	
US Regional Update	124
<i>Patrick Naulleau</i>	
IEUVI Update	136
<i>Paolo Gargini</i>	
Asia Pacific Regional Update - Japan, Korea and Taiwan Regional Update	183
<i>Ichiro Mori</i>	

TECHNICAL SESSION: EXPOSURE TOOL

EUV Alpha Demo Tools – Stepping Stones Towards Volume Production	199
<i>H. Meiling, S. Lok, B. Hultermans, E. van Setten, B. Pierson, K. Cummings, C. Wagner, N. Harned</i>	
Nikon EUVL Development Progress Update	230
<i>Takaharu Miura</i>	
Development Status of Canon's Full-Field EUVL Tool	264
<i>Shigeyuki Uzawa, Tokuyuki Honda, Hideki Morishima, Takayuki Hasegawa</i>	

TECHNICAL SESSION: RESIST I

EUV Resist Performance on the ASML ADT and LBNL MET	291
<i>Bill Pierson, Tom Wallow, Hiroyuki Mizuno, Anita Fumar-Pici, Linda Ohara, Karen Petrillo, Koen van Ingen-Schenau, Steve Hansen, Sang-In Han, Robert Watso, Lior Huli, Obert Wood, Joerg Mallmann, Bart Kessels, Robert Routh, Kevin Cummings</i>	
The SEMATECH Berkeley MET: Learning at the 22 nm Node	312
<i>Patrick Naulleau, Chris Anderson, Paul Denham, Simi George, Ken Goldberg, Brian Hoef, Gideon Jones, Dimitra Niakoula, Ryan Miyakawa, John Roller, Chawon Koh, Warren Montgomery, Stefan Wurm, Bruno La Fontaine, Tom Wallow, Andy Ma, Joo-on Park</i>	
Evaluation of EUV Resists at Selete	335
<i>Hiroaki Oizumi, Daisuke Kawamura, Koji Kaneyama, Shinji Kobayashi, Toshiro Itani</i>	
Advances in Resist Testing at PSI EUV-IL Exposure Tool	363
<i>Vaida Auželyte, Pratap Sahoo, Menouer Saidani, Anja Weber, Harun H. Solak</i>	
Positive and Negative Tone Molecular Resists for 22-nm Node EUVL Patterning	376
<i>Richard Lawson, Cheng-Tsung Lee, Laren M. Tolbert, Clifford L. Henderson</i>	

TECHNICAL SESSION: RESIST II

Sub-22nm Half-Pitch (HP) EUV Resist Imaging Results	398
<i>Chawon Koh, Stefan Wurm, Joo-on Park, Andy Ma, Patrick Naulleau</i>	
Corner Rounding in Photoresists for Extreme Ultraviolet Lithography	426
<i>Christopher N. Anderson, Patrick P. Naulleau, Thomas Wallow, Yunfei Deng</i>	

Reconciling Resist Resolution Metrics	487
<i>Gregg M. Gallatin, Patrick P. Naulleau, Christopher N. Anderson</i>	
Feasibility Study on High-Sensitivity Chemically Amplified Resist by Polymer Absorption Enhancement in Extreme Ultraviolet Lithography	505
<i>T. Kozawa, K. Okamoto, J. Nakamura, S. Tagawa</i>	

TECHNICAL SESSION: COST OF OWNERSHIP

Cost Implications of EUV Lithography Technology Decisions	520
<i>Andrea F. Wüest, Andrew J. Hazelton, Greg Hughes, Lloyd C. Litt, Frank Goodwin</i>	

Volume 2

TECHNICAL SESSION: MASK I

An Overview of a Development Program for EUVL Mask Technologies in Selete	551
<i>Osamu Suga, Tsuneo Terasawa, Hiroyuki Shigemura, Takao Taguchi, Iwao Nishiyama, Ichiro Mori</i>	
Development Status of EUVL Mask Blank and Substrate	563
<i>Yoshiaki Ikuta</i>	
Multilayer Defect Compensation to Enable Quality Masks for EUVL Production	583
<i>Ted Liang, Eric Gullikson</i>	
EUV Reticle Contamination and Cleaning	602
<i>U. Okoroanyanwu, E. Langer, A. Fumar-Pici, T. Wallow, O. Wood, B. La Fontaine, C. Holfeld, J. H. Peters, M. Bender, M. Rossinger, S. Trogisch, F. Goodwin, A. Wüest, S. Huh, G. Denbeaux, Y. Fan, A. Antohe, L. Yankulin, R. Garg, K. Goldberg, P. Naulleau</i>	
High Transmission EUVL Pellicle Development	623
<i>Yashesh A. Shroff, Pei-Yang Yan, Farhad Salamassi, Eric Gullikson</i>	
Applying Thinner Absorber to the EUVL Mask: EUV Printability and Integration Issues	646
<i>Hwan-Seok Seo, Dong Gun Lee, Hoon Kim, Sungmin Huh, Byung-Sup Ahn, Hakseung Han, Dongwan Kim, Seong-Sue Kim, Han Ku Cho</i>	

TECHNICAL SESSION: MASK II

Study of Pit Defect Formation on EUV Blank Substrates	663
<i>Abbas Rastegar, Sean Eichenlaub, Arun John Kadaksham, Matt House, Brian Cha, Henry Yun</i>	
Investigation of a Compensation Method for Pattern Placement Shifts of Chucked EUVL Masks	689
<i>J. Sohn, K. Orvek, R. Engelstad, A. Lyons, J. Hartley</i>	
High Throughput Defect Mitigation	709
<i>Patrick Kearney, C. C. Lin, T. Sugiyama, H. Yun, R. Randive, I. Reiss, P. Mirkarimi, E. Spiller, A. Hayes</i>	
Characterization of EUV Mask Defects: Printability and Repair Process	721
<i>Hakseung Han, Donggun Lee, Hwan-Seok Seo, Kenneth A. Goldberg, Hoon Kim, Byung-Sub Ahn, In-Yong Kang, Wonil Cho, Sanghyeon Lee, Suyoung Lee, Geunbae Kim, Dongwan Kim, Seong-Sue Kim, HanKu Cho</i>	
Mask Defect Printability in Full Field EUV Lithography – Part 2	742
<i>R. Jonckheere, F. Iwamoto, N. Stepanenko, A. M. Goethals, K. Ronse</i>	

TECHNICAL SESSION: METROLOGY/INSPECTION

A Practical Approach to EUV Reticle Inspection	774
<i>Anna Tchikoulaeva, et.al.</i>	
Development of Actinic Mask Blank Inspection Technology at Selete	805
<i>Tsuneo Terasawa, Takeshi Yamane, Teruo Iwasaki, Toshihiko Tanaka, Osamu Suga, Toshihisa Tomie</i>	
EUVL Blank Defect Inspection Capability at Intel	829
<i>Andy Ma, Ted Liang, Seh-Jin Park, Guojing Zhang, Tomoya Tamura, Kazunori Omata</i>	
Analysis of Sub-22-nm Aerial Image Using Coherent Scattering Microscopy	848
<i>Dong Gun Lee, Junki Kishimoto, Takeo Watanabe, Hiroo Kinoshita, Hwan-Seok Seo, Dongwan Kim, Seong-Sue Kim, HanKu Cho</i>	
Aerial Image Linewidth Measurement Capabilities of the Actinic Inspection Tool	867
<i>Kenneth A. Goldberg, Iacopo Mochi, Patrick Naulleau, Bruno LaFontaine, Sungmin Huh</i>	

TECHNICAL SESSION: SOURCE I

Laser Produced Plasma Source System Development	890
<i>David C. Brandt, et.al.</i>	
CO₂ Laser-produced Sn Plasma Source for EUV Lithography	916
<i>Akira Endo, et.al.</i>	
EUV Sources based on DPP	935
<i>Marc Corthout, Masaki Yoshioka</i>	
Time-Multiplexed Solid-State Laser-driven EUV Sources for Beta-Tools and HVM	956
<i>K. Takenoshita, R. Bernath, R. Kamptaprasad, J. Szilagy, S. A. George, J. Cunado, M. Richardson, B. Fulford, I. Henderson, N. Hay, S. Ellwi</i>	

TECHNICAL SESSION: SOURCE II

Guidelines and Promising Approach for LPP-EUV Light Source for HVM	975
<i>K. Nishihara, et.al.</i>	
Technological Aspects of Sn RDE Source Development for HVM Lithography	996
<i>V. M. Borisov, G. N. Borisova, A. S. Ivanov, Yu. B. Kirukhin, O. B. Khristoforov, V. A. Mishchenko, A. V. Prokofiev, A. Yu. Vinokhodov</i>	
Spectral Purity Filter Development for EUV HVM	1018
<i>A. Yakunin, V. Banine, N. Salashchenko, E. Klunokov, A. Lopatin, V. Luchin, N. Tsybin, L. Sjmaenok, W. Soer, M. Jak</i>	
Design and Fabrication Considerations of EUVL Collectors for HVM	1041
<i>G. Bianucci, J. Kools, G. Salmaso, F. E. Zocchi</i>	

TECHNICAL SESSION: CONTAMINATION AND PARTICLES

Strategy for Minimizing EUV Optics Contamination During Exposure	1055
<i>N. Harned, R. Moors, M. van Kampen, V. Banine, J. Huijbregtse, R. Vanneer, A. Kempen, D. Ehm, R. Verberk, E. te Sligte, A. Storm</i>	
Effective Debris Detection, Mitigation and Cleaning Methods for Source - Collector Optics	1077
<i>David N. Ruzic, Ramasamy Raju, J. Sporre, H. Shin, W. M. Lytle, M. J. Neumann</i>	

Volume 3

TECHNICAL SESSION: CONTAMINATION AND PARTICLES (cont.)

Shielded Plasma's for Cleaning EUV Mirrors	1119
<i>N. B. Koster, R. Koops, K. Agovic, F. P. J. de Groote, F. P. Wieringa, M. G. H. Meijerink</i>	
Carbon Accumulation on Model MLM Cap Layer: Interaction of Benzene Vapor with TiO₂ Surface	1141
<i>Boris Yakshinskiy, Shimon Zalkind, Theodore E. Madey</i>	
Progress on EUV Reticle Dual Pod Carriers for use in the Fab and Exposure Tools	1155
<i>John Zimmerman, Long He</i>	

TECHNICAL SESSION: EXPOSURE TOOL EVALUATION

Lithographic Performance of Selete's Full Field EUV Exposure Tool	1174
<i>Kazuo Tawarayama, Hajime Aoyama, Takashi Kamo, Shunko Magoshi, Yuusuke Tanaka, Seiichiro Shirai, Hiroyuki Tanaka</i>	
Full-field Patterning Test with ADT for 30-nm Node Device Application	1201
<i>Doohoon Goo, Insung Kim, Joo-On Park, Jeonghoon Lee, Changmin Park, Jinhong Park, Jeong-Ho Yeo, Sungwoon Choi, Woosung Han</i>	
Flare Evaluation of an ASML Alpha Demo Tool	1227
<i>Hiroyuki Mizuno, Martin Burkhardt, Chiew-seng Koay, Greg McIntyre, Tim Brunner, Bruno La Fontaine, Yunfei Deng, Obert Wood</i>	
Implementing Full field EUV Lithography using the ADT	1242
<i>Anne-Marie Goethals, et.al.</i>	

TECHNICAL SESSION: OPTICS

Improvement of Optics for EUV Exposure Tools	1275
<i>Katsuhiko Murakami, Tetsuya Oshino, Hiroyuki Kondo, Hiroshi Chiba, Kazushi Nomura</i>	
Optics for EUV Lithography	1300
<i>Peter Kuerz, et.al.</i>	
Projection Optics for a 0.5-NA Microstepper Upgrade	1321
<i>Michael Goldstein, Russ Hudyma, Patrick Naulleau</i>	
Projection Architectures for High NA EUVL	1341
<i>Russ Hudyma, Mike Thomas, Mark Schwarz</i>	

CLOSING ADDRESS

2008 EUVL Symposium - Closing Address	1367
<i>Stefan Wurm, Obert Wood, Patrick Naulleau</i>	

POSTERS: EXPOSURE TOOL

Ultra-High Resolution Extreme Ultraviolet Lithography by Incoherent to Coherent Conversion	1389
<i>Christopher N. Anderson, Patrick P. Naulleau</i>	
MOSAIC - A New Way to Measure Optical Aberrations	1390
<i>Christopher N. Anderson, Patrick P. Naulleau</i>	
First Italian EUV Micro Exposure Tool at 14.4 nm based on Kr DMS	1391
<i>S. Bollanti, P. Di Lazzaro, F. Flora, L. Mezi, D. Murra, A. Torre</i>	
Lithographic Modeling of a 0.5-NA Microstepper Optic	1416
<i>Patrick Naulleau, Michael Goldstein, Russ Hudyma</i>	
Impact of Flare and Aberrations on Patterning Performance - Simulation with the EUV Full Field Alpha Tool Conditions	1417
<i>Liping Ren, Frank Goodwin, Stefan Wurm, Chawon Koh, Sudharshanan Raghunathan, John Hartley</i>	
Multiple Catadioptric Simplified Extreme Ultraviolet Whole Lithography Machine and System	1418
<i>Wynn L. Bear, Xiangwen Xiong</i>	
Reliability and Productivity Improvements on the Intel MET	1433
<i>Roman Caudillo, Jeanette Roberts, Terence Bacuita, Gilroy Vandentop</i>	
Composite Double Reflection Simplified Extreme Ultraviolet Whole Lithography Machine and System	1449
<i>Wynn L. Bear, Xiangwen Xiong</i>	

POSTERS: SOURCE

Spectral Purity Filter Life-Time Testing on EQ-10 Source	1461
<i>Chuck Schietinger, Dave Grove, Travis Ayers, Matthew Partlow, Debbie Gustafson</i>	
Dependence of Laser Parameter on Conversion Efficiency in High-Repetition-Rate Laser-Ablation-Discharge EUV Source	1462
<i>Takuma Yokoyama, Hiroshi Mizokoshi, Yusuke Teramoto, Daiki Yamatani, Hiroto Sato, Kazuaki Hotta</i>	
EUV Spectrometers for Source Development, Characterization and Optimization	1479
<i>Scott Bergeson, Bryce Allred, Jershon Lopez, Jeffrey Kemp, Larry Knight, Alexander Shevelko</i>	
High Power from Low Etendue EUV Light Sources	1480
<i>Michael Goldstein, Stefan Wurm, Frank Goodwin</i>	
The Characterization of the Ion Beam from a Sn-based DPP with Respect to the Ignition Parameters	1481
<i>K. Gielissen, Y. Sidelnikov, W. Soer, M. van Herpen, D. Glushkov, V. Banine, J. van der Mullen</i>	
Present Status of Laser-produced Plasma EUV Light Source	1482
<i>Hiroshi Komori, et.al.</i>	
Performance Evaluation of EUV SFET Source Collector Module	1483
<i>Shunko Magoshi, Seiichiro Shirai, Hideto Mori, Kazuo Tawarayama, Yuusuke Tanaka, Hiroyuki Tanaka</i>	

POSTERS: RESISTS

Development of New Negative-tone Molecular Resists based on Alkylphenyl Callxarene for EUVL	1499
<i>Masatoshi Echigo, Dai Oguro, Hiroaki Oizumi, Toshiro Itani</i>	
Survey and Comparison of Deprotection Blur Metrics for Extreme Ultraviolet Photoresists	1500
<i>Christopher N. Anderson, Patrick P. Naulleau</i>	
Investigation of CA Resist Decomposition by EUV and EB Exposure	1501
<i>Daiju Shiono, Taku Hirayama, Hideo Hada, Junichi Onodera, Takeo Watanabe, Hiroo Kinoshita</i>	
Novel Polyphenol Base Molecular Resist Having High Thermal Resistance	1513
<i>Taku Hirayama, Takeyoshi Mimura, Jun Iwashita, Makiko Irie, Daiju Shiono, Hideo Hada, Takeshi Iwai</i>	
Electrons in EUV Resist Activation	1529
<i>Theodore E. Madey, B. V. Yakshinskiy, E. Loginova, L. Sanche, P. Cloutier, R. Brainard, A. Wuest</i>	
DUV Source Integration into the 0.3 NA Berkeley SEMATECH MET for OOB Exposure Studies	1530
<i>Simi A. George, Patrick P. Naulleau, Senajith Rekawa, Drew Kemp</i>	
Development of Novel Positive-tone Photoresists for EUVL	1531
<i>Takanori Owada, Akinori Yomogita, Takashi Kashiwamura, Hiroaki Oizumi, Toshiro Itani</i>	
Relation between Acid Diffusion and Resolution in Chemically Amplified EUV Resists	1542
<i>Y.uuki Hirai, Makoto Shimizu, Ken Maruyama, Toshiyuki Kai, Tsutomu Shimokawa, Toshiro Itani, Daisuke Kawamura</i>	
EUV Photoresists Twice as Fast as Previously Thought	1560
<i>Patrick Naulleau, Eric Gullikson, Andrew Aquila, Paul Denham, Simi George, Drew Kemp, Dimitra Niakoula, Seno Rekawa</i>	
EUV Resist Outgassing Quantification and Qualification Analysis Methods	1561
<i>Shinji Kobayashi, Julius Joseph Santillan, Hiroaki Oizumi, Toshiro Itani</i>	
Development of Partially Fluorinated EUV Resist Polymers for Sensitivity Improvement	1562
<i>Takashi Sasaki, Osamu Yokokoji, Takeo Watanabe, Hiroo Kinoshita</i>	

POSTERS: MASK

Mask Effects on Line-Edge Roughness (LER)	1563
<i>Patrick P. Naulleau, Kenneth A. Goldberg, Iacopo Mochi, Guojing Zhang</i>	
Experimental Study on Flatness of Electrostatically Chucked Reticle	1564
<i>K. Ota, T. Taguchi, M. Amemiya, N. Nishimura, O. Suga</i>	
FIB Mask Repair Technology for EUV Lithography	1565
<i>Tsuyoshi Amano, Yasushi Nishiyama, Hiroyuki Shigemura, Tsuneo Terasawa, Osamu Suga, Kensuke Shiina, Fumio Aramaki, Ryoji Hagiwara, Anto Yasaka</i>	
Analysis of Entrapped Object Size Effects on Out-of-Plane Distortion of the EUVL Mask in Electrostatic Chucking	1583
<i>S. Lee, T. Yamamoto, K. Ota, N. Nishimura, T. Taguchi, I. Nishiyama, O. Suga, S. Warisawa, S. Ishihara</i>	

POSTERS: DEFECT INSPECTION

A Study of Optical Inspection on EUVL Mask for 32 nm Half Pitch Node Device and Beyond	1593
<i>Yukiyasu Arisawa, Hiroyuki Shigemura, Tsuyoshi Amano, Hajime Aoyama, Toshihiko Tanaka, Osamu Suga</i>	

POSTERS: RETICLE CONTAMINATION

Characterization of EUV-Deposited Carbonaceous Contamination	1611
<i>Toshihisa Anazawa, Yasushi Nishiyama, Hiroaki Oizumi, Osamu Suga, Iwao Nishiyama</i>	
Experimental Study of Particle-free Mask Handling Techniques using the MPE Tool	1631
<i>Mitsuaki Amemiya, Kazuya Ota, Takao Taguchi, Osamu Suga</i>	

POSTERS: OPTICS AND ML COATINGS

Iterative Procedure for in situ Optical Testing using an Incoherent Source	1632
<i>Ryan Miyakawa, Patrick P. Naulleau, Avidah Zakhor</i>	

Lateral Shearing Interferometry for EUV Optical Testing	1633
<i>Ryan Miyakawa, Patrick P. Naulleau, Ken Goldberg</i>	

POSTERS: OPTICS CONTAMINATION

Resist Outgassing Measurements and Calibrations for High Volume Manufacturing	1634
<i>Greg Denbeaux, Alin Antohe, Rashi Garg, Chimaobi Mbanaso, LeonidYankulin, Yu-Jen Fan, Kevin Orvek, Andrea Wüest</i>	
Experiment of Contamination Generation by EUV Irradiation with the Use of High-mass Hydrocarbon Gas	1648
<i>Masahito Niibe, Keigo Koida</i>	
EUVL Optics Contamination from Resist Outgassing: Status Overview	1650
<i>Kevin Orvek, Greg Denbeaux, Alin Antohe, Rashi Garg, Chimaobi Mbanaso</i>	
Moisture and Hydrocarbon Management for EUVL Tools: Ultra High Vacuum and Purge Gas Purification Solutions	1666
<i>Andrea Conte, Cristian Landoni, Paolo Manini, Larry Rabellino, Sarah Riddle</i>	

POSTERS: DEVICE INTEGRATION

Characterization of New EUV Stable Silicon Photodiodes	1667
<i>F. Scholze, C. Laubis, F. Sarubbi, Lis K. Nanver, S. N. Nihitjanov</i>	

POSTERS: COST OF OWNERSHIP

The Comprehensive Cost for the Mainstream NGL and Simplified Extreme Ultraviolet Lithography Method	1668
<i>Wynn L. Bear, Xiangwen Xiong</i>	

Author Index